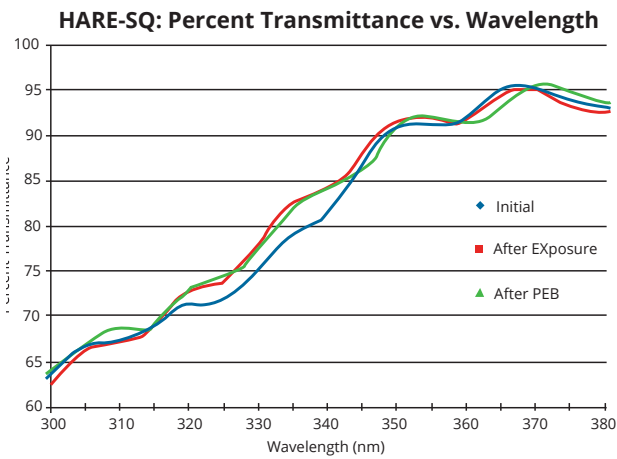
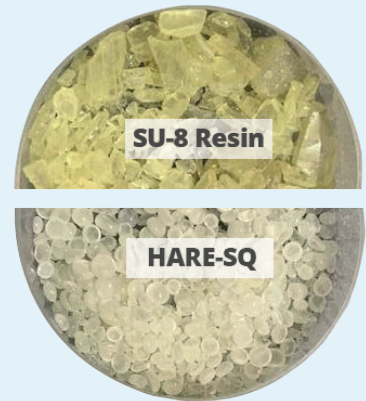


HARE-SQ NEGATIVE TONE RESIST

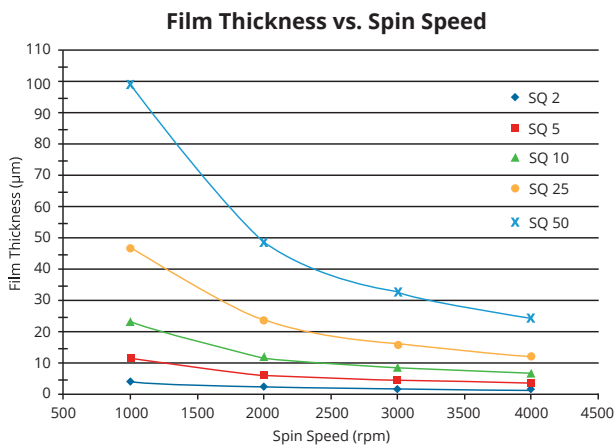
HARE-SQ (High Aspect Ratio Epoxy / Superior Quality) is an epoxy based negative photoresist designed for polymeric MEMS, microfluidics, micromachining and other microelectronic applications. The HARE-SQ system is designed for use in thick film applications of 2 to 100 μm , and is ideal for use in permanent applications in which the photoresist remains within the finished device.



- Clearer layer (cleaner than SU-8 Resin)
- Lower opacity (Higher transparency – less dosing power/power intensity required)
- Fewer particles
- Fewer micro-bubbles
- More consistent product

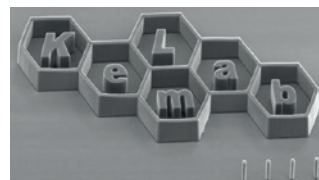
ADVANTAGES

- The HARE-SQ photoresist uses an epoxy resin with superior cleanliness and excellent reproducibility
- Consistent surface energy of cross-linked resist (an important property for microfluidic applications).
- Fully compatible with SU-8 processes.



SUBSTRATES

HARE SQ adheres to variety of substrates; including silicon, gold, aluminum, chromium and copper. Proper substrate cleaning & dehydration improve adhesion.



Logo & posts in 50 μm film



5 μm dense line/space in 25 μm film